Hui Sun

List of Publications by Year
in descending order

47	665	471509 17	677142 22
papers	citations	h-index	g-index

47	47	47	658
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Modification of TiO2 nanotubes by WO3 species for improving their photocatalytic activity. Applied Surface Science, 2015, 343, 181-187.	6.1	37
2	Light enhanced moisture degradation of perovskite solar cell material CH₃NH₃PbI₃. Journal of Materials Chemistry A, 2019, 7, 27469-27474.	10.3	37
3	Microstructures and optoelectronic properties of nickel oxide films deposited by reactive magnetron sputtering at various working pressures of pure oxygen environment. Ceramics International, 2017, 43, S369-S375.	4.8	30
4	Optoelectronic properties of p-type NiO films deposited by direct current magnetron sputtering versus high power impulse magnetron sputtering. Applied Surface Science, 2020, 508, 145106.	6.1	30
5	Optoelectronic properties of Cu3N thin films deposited by reactive magnetron sputtering and its diode rectification characteristics. Journal of Alloys and Compounds, 2019, 789, 428-434.	5.5	29
6	High transmittance in IR region of conductive ITO/AZO multilayers deposited by RF magnetron sputtering. Ceramics International, 2018, 44, 6769-6774.	4.8	27
7	Optoelectronic properties of delafossite structure CuCr_{0.93}Mg_{0.07}O₂sputter deposited coatings. Journal Physics D: Applied Physics, 2016, 49, 185105.	2.8	26
8	p-type cuprous oxide thin films with high conductivity deposited by high power impulse magnetron sputtering. Ceramics International, 2017, 43, 6214-6220.	4.8	25
9	Towards delafossite structure of Cuâ€“Crâ€“O thin films deposited by reactive magnetron sputtering: Influence of substrate temperature onÂoptoelectronics properties. Vacuum, 2015, 114, 101-107.	3.5	22
10	Microstructures and optoelectronic properties of CuxO films deposited by high-power impulse magnetron sputtering. Journal of Alloys and Compounds, 2016, 688, 672-678.	5.5	22
11	Electrical and magnetic properties of (Al, Co) co-doped ZnO films deposited by RF magnetron sputtering. Surface and Coatings Technology, 2019, 359, 390-395.	4.8	20
12	Optoelectronic properties of an AZO/Ag multilayer employed as a flexible electrode. Ceramics International, 2021, 47, 5671-5676.	4.8	19
13	High photodegradation ability of dyes by Fe(III)-tartrate/TiO2 nanotubular photocatalyst supported via photo-Fenton reaction. Journal of Photochemistry and Photobiology A: Chemistry, 2017, 334, 20-25.	3.9	18
14	p-type conductive NiOx: Cu thin films with high carrier mobility deposited by ion beam assisted deposition. Ceramics International, 2018, 44, 3291-3296.	4.8	18
15	Review in optoelectronic properties of p-type CuCrO2 transparent conductive films. Surfaces and Interfaces, 2021, 22, 100824.	3.0	18
16	Influence of carbon content on the mechanical properties of TiCNâ€“Cu nanocomposite coatings prepared by multi-arc ion plating. Vacuum, 2021, 187, 110139.	3.5	18
17	Effect of annealing temperature on the optoelectronic properties and structure of NiO films. Ceramics International, 2022, 48, 2820-2825.	4.8	18
18	Contribution of enhanced ionization to the optoelectronic properties of p-type NiO films deposited by high power impulse magnetron sputtering. Journal of the European Ceramic Society, 2019, 39, 5285-5291.	5.7	17

#	Article	IF	Citations
19	Optoelectronic Properties and the Electrical Stability of Ga-Doped ZnO Thin Films Prepared via Radio Frequency Sputtering. Materials, 2016, 9, 987.	2.9	14
20	Ag composition gradient CuCr0.93Mg0.07O2/Ag/CuCr0.93Mg0.07O2 coatings with improved p-type optoelectronic performances. Journal of Materials Science, 2017, 52, 11537-11546.	3.7	14
21	Structure, mechanical and tribological properties, and oxidation resistance of TaC/a-C:H films deposited by high power impulse magnetron sputtering. Ceramics International, 2020, 46, 24986-25000.	4.8	14
22	Synthesis and characterization of n-type NiO:Al thin films for fabrication of p-n NiO homojunctions. Journal Physics D: Applied Physics, 2018, 51, 105109.	2.8	13
23	Impact of active layer thickness of nitrogen-doped Inâ€“Snâ€“Znâ€“O films on materials and thin film transistor performances. Journal Physics D: Applied Physics, 2018, 51, 175101.	2.8	13
24	Thickness-dependent optoelectronic properties of CuCr0.93Mg0.07O2 thin films deposited by reactive magnetron sputtering. Materials Science in Semiconductor Processing, 2017, 63, 295-302.	4.0	12
25	The Influence of Oxygen Flow Ratio on the Optoelectronic Properties of p-Type Ni1â^'xO Films Deposited by Ion Beam Assisted Sputtering. Coatings, 2018, 8, 168.	2.6	12
26	Research Progress of p-Type Oxide Thin-Film Transistors. Materials, 2022, 15, 4781.	2.9	11
27	The electrical stability of In-doped ZnO thin films deposited by RF sputtering. Journal Physics D: Applied Physics, 2017, 50, 045102.	2.8	10
28	The adhesion strength and mechanical properties of SiC films deposited on SiAlON buffer layer by magnetron sputtering. Surface and Coatings Technology, 2019, 360, 116-120.	4.8	10
29	Mechanical properties, thermal stability and oxidation resistance of HfC/a-C:H films deposited by HiPIMS. Journal of Alloys and Compounds, 2020, 847, 156538.	5.5	10
30	p-type semi-transparent conductive NiO films with high deposition rate produced by superimposed high power impulse magnetron sputtering. Ceramics International, 2020, 46, 27695-27701.	4.8	10
31	Research on adhesion strength and optical properties of SiC films obtained via RF magnetron sputtering. Chinese Journal of Physics, 2020, 64, 79-86.	3.9	10
32	Transparent Conductive p-Type Cuprous Oxide Films in Vis-NIR Region Prepared by Ion-Beam Assisted DC Reactive Sputtering. Coatings, 2020, 10, 473.	2.6	9
33	Comparison of microstructural and optoelectronic properties of NiO:Cu thin films deposited by ion-beam assisted rf sputtering in different gas atmospheres. Thin Solid Films, 2019, 677, 103-108.	1.8	8
34	High power impulse magnetron sputtering growth processes for copper nitride thin film and its highly enhanced UV - visible photodetection properties. Journal of Alloys and Compounds, 2022, 896, 162924.	5.5	8
35	Periodic mesoporous organosilica coupled with chlorin e6 and catalase for enhanced photodynamic therapy to treat triple-negative breast cancer. Journal of Colloid and Interface Science, 2022, 610, 634-642.	9.4	8
36	Influence of power frequency on the performance of SiC thin films deposited by pulsed DC magnetron sputtering. Journal of Adhesion Science and Technology, 2019, 33, 2181-2190.	2.6	7

#	Article	IF	Citations
37	Influence of Sputtering Power on the Electrical Properties of In-Sn-Zn Oxide Thin Films Deposited by High Power Impulse Magnetron Sputtering. Coatings, 2019, 9, 715.	2.6	6
38	The Optoelectronic Properties of p-Type Cr-Deficient Cu[Cr0.95â˜'xMg0.05]O2 Films Deposited by Reactive Magnetron Sputtering. Materials, 2020, 13, 2376.	2.9	6
39	Research Progress of Transparent Electrode Materials with Sandwich Structure. Materials, 2021, 14, 4097.	2.9	6
40	Highly transparent and conductive p-type CuI films by optimized solid-iodination at room temperature. Nanotechnology, 2022, 33, 105706.	2.6	6
41	Absorption Amelioration of Amorphous Si Film by Introducing Metal Silicide Nanoparticles. Nanoscale Research Letters, 2017, 12, 224.	5.7	5
42	In-Sn-Zn Oxide Nanocomposite Films with Enhanced Electrical Properties Deposited by High-Power Impulse Magnetron Sputtering. Nanomaterials, 2021, 11, 2016.	4.1	4
43	Pico-molar level detection of copper ion with extraordinarily high response by Ti-doped copper nitride fabricated via high power impulse magnetron sputtering. Sensors and Actuators B: Chemical, 2022, 360, 131632.	7.8	3
44	Enhanced photocatalytic activity by photo-Fenton reaction: towards TiO₂ nanotubes sensitized by Fe(III)-tartrate. Journal Physics D: Applied Physics, 2019, 52, 175302.	2.8	2
45	Influence of annealing temperature on the optoelectronic properties of ITZO thin films. Nanotechnology, 2021, 32, 405701.	2.6	2
46	Tuning the Electrical Properties of NiO Thin Films by Stoichiometry and Microstructure. Coatings, 2021, 11, 697.	2.6	1
47	Design of flexible resistance sensor based on mesh convex microstructure. Journal Physics D: Applied Physics, 0, , .	2.8	0